Electronic Supplementary Information

Structural and Optoelectronic Characteristics of β-Ga₂O₃ Epitaxial Films with Zn Alloying and Subsequent Oxygen Annealing

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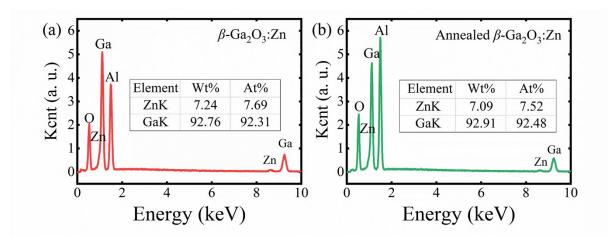


Figure S1 EDS spectra of as-grown and annealed β -Ga₂O₃:Zn thin films.

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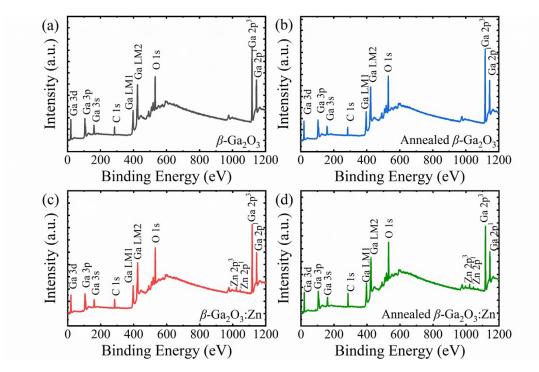


Figure S2 XPS survey spectra of (a) pure β-Ga₂O₃, (b) annealed β-Ga₂O₃, (c) β-Ga₂O₃:Zn and (d) annealed β-Ga₂O₃:Zn films.

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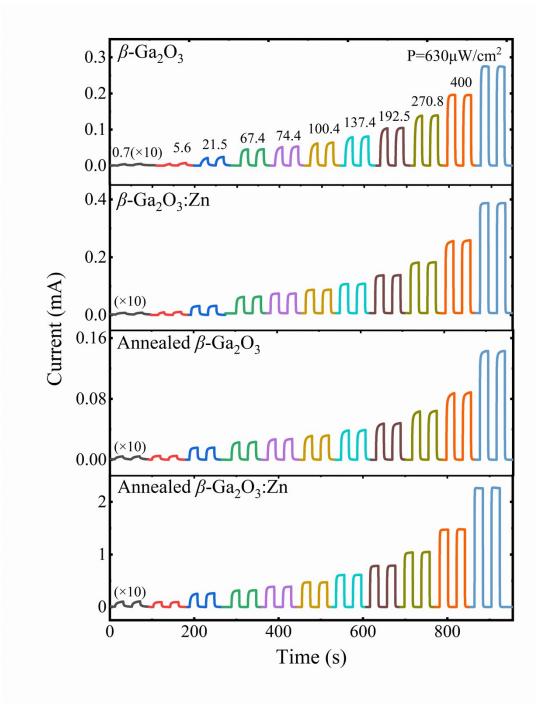


Figure S3 Time-dependent photocurrent characteristics of the photodetectors under 254 nm illuminations with different light intensities from 0.7 μ W/cm² to 630 μ W/cm² at 10 V bias.